

## IMPRINT LITHOGRAPHY TEMPLATE HAVING OPAQUE ALIGNMENT MARKS

### ABSTRACT OF THE DISCLOSURE

[0045] The present invention is directed to providing a template with alignment marks that are opaque to selective wavelength of light. In one embodiment, a template is provided having patterning areas and a template, with the template mark being formed from metal and disposed outside of the patterning areas. The alignment marks may be surrounded by a moat to prevent curable liquid from being in superimposition therewith during imprinting. In this manner, opaque alignment marks may be employed without degrading the quality of the pattern formed during imprinting.